

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	49	"6130750"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:41
L2	526501	resist photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:41
L3	526501	resist photoresist photo adj resist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:42
L4	37	1 and 3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:42
L5	915722	(alignment registration) (overlay same (error uncertainty))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:53
L6	914334	(alignment registration)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 17:03
L7	526501	resist photoresist photo adj resist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 17:03
L8	20690	L6 adj mark	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 17:03
L9	2037	L8 with L7	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 17:03
L10	615486	wavelength lambda lamda	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 17:03

L11	78743	L10 near2 L10 sub adj L10	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 17:03
L12	219	L9 and L11	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 17:03
L13	169798	L6.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 17:03
L14	135	L12 and L13	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 17:14

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L15	905	((resist photoresist photo adj resist) AND (alignment registration) (overlay same (error uncertainty)) AND (wavelength lambda lamda) AND (thick\$4 height) AND (pitch interval gap distance length spacing feature period) AND (continuous\$3 planar unpattern\$4)).clm.	US-PGPUB	OR	ON	2005/12/05 17:31
L18	136	((resist photoresist photo adj resist) SAME (layer film) AND (alignment registration) SAME (mark) (overlay SAME (error uncertainty)) AND (wavelength lambda lamda) AND (thick\$4 height) SAME (resist photoresist photo adj resist) AND (pitch interval gap distance length spacing feature period) SAME (wavelength lambda lamda) AND (continuous\$3 planar unpattern\$4) SAME (resist photoresist photo adj resist)).clm.	US-PGPUB	OR	ON	2005/12/05 17:29
L20	145	((resist photoresist photo adj resist) SAME (layer film mask) AND (alignment registration) WITH (mark) (overlay SAME (error uncertainty)) AND (wavelength lambda lamda) AND (thick\$4 height) SAME (resist photoresist photo adj resist) AND (pitch interval gap distance length spacing feature period) SAME (wavelength lambda lamda) AND (continuous\$3 planar unpattern\$4) SAME (resist photoresist photo adj resist)).clm.	US-PGPUB	OR	ON	2005/12/05 17:31
L24	120	((resist photoresist photo adj resist) NEAR2 (layer film mask) AND (alignment registration) NEAR2 (mark) (overlay ADJ2 (error uncertainty)) AND (wavelength lambda lamda) AND (thick\$4 height) NEAR2 (resist photoresist photo adj resist) AND (pitch interval gap distance length spacing feature period) WITH (narrow\$2 wide\$2 big\$2 great\$2 large\$2 small\$2 thick\$2 thin\$2 different varying vari\$4 increas\$4 decreas\$4) WITH (wavelength lambda lamda) AND (continuous\$3 planar unpattern\$4) WITH (resist photoresist photo adj resist)).clm.	US-PGPUB	OR	ON	2005/12/05 17:42
L30	0	(((resist photoresist photo adj resist) AND (layer film mask)) AND (((alignment registration) SAME (mark)) (overlay SAME (error uncertainty))) AND (wavelength lambda lamda) AND ((thick\$4 height) SAME (resist photoresist photo adj resist)) AND ((pitch interval gap distance length spacing feature period) AND (wavelength lambda lamda)) AND ((continuous\$3 planar unpattern\$4) SAME (resist photoresist photo adj resist))).clm.	US-PGPUB	OR	ON	2005/12/05 17:47
L31	0	(((resist photoresist photo adj resist) AND (layer film mask)) AND (((alignment registration) SAME (mark)) (overlay SAME (error uncertainty))) AND (wavelength lambda lamda) AND ((thick\$4 height) AND (resist photoresist photo adj resist)) AND ((pitch interval gap distance length spacing feature period) AND (wavelength lambda lamda)) AND ((continuous\$3 planar unpattern\$4) SAME (resist photoresist photo adj resist))).clm.	US-PGPUB	OR	ON	2005/12/05 17:47

L32	4	(((resist photoresist photo adj resist) AND (layer film mask)) AND (((alignment registration) SAME (mark)) (overlay SAME (error uncertainty))) AND (wavelength lambda lambda) AND ((thick\$4 height) AND (resist photoresist photo adj resist)) AND ((pitch interval gap distance length spacing feature period) AND (wavelength lambda lambda)) AND ((continuous\$3 planar unpattern\$4) AND (resist photoresist photo adj resist))).clm.	US-PGPUB	OR	ON	2005/12/05 17:47
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